

## AMENDMENTS TO THE CLAIMS

1. (currently amended) A product produced by the process comprising the steps of:

applying a layer of photo-sensitized epoxy to the first side of a substrate having a first and second side, wherein the layer of epoxy has a thickness of at least 100 micrometers and the substrate is at least partially transparent to light to which the photo-sensitized epoxy is sensitive;

exposing at least one region within the layer of photo-sensitized epoxy with light incident upon the second side of the substrate sufficient to produce at least one region of polymerization of varying thickness within the layer of photo-sensitized epoxy, such that upon removal of the non-polymerized regions of the layer, following polymerization of the one region, the resulting three-dimensional structure has a continuously varying thickness and a smoothly varying topography, with a thickness of at least 100 micrometers.

2. (cancelled)

3. (currently amended) A three-dimensional article, comprising:

a substrate having a first side and a second side;

a photo-sensitized epoxy layer applied on the first side of the substrate, wherein the epoxy layer has a thickness of at least 100 micrometers and the substrate is at least partially transparent to light to which the photo-sensitized epoxy is sensitive, wherein the photo-sensitized epoxy layer has been exposed to light incident on the second side of the substrate sufficient to produce at least one region of polymerization of varying thickness within the layer of photo-sensitized epoxy, with non-polymerized portions of the layer having been removed following polymerization of the one region, to produce a resulting three-dimensional structure with a continuously varying thickness and a smoothly varying topography, and a thickness of at least 100 micrometers.

4. (cancelled)

5. (currently amended) A three-dimensional article, comprising:

a substrate having a first side and a second side;

a negative photo-sensitized epoxy layer applied on the first side of the substrate, wherein the layer of epoxy has a thickness of at least 100 micrometers and wherein the substrate is at least partially transparent to light to which the photo-sensitive epoxy is sensitive, and then processed, including exposure of the photo-sensitive epoxy layer by light incident on the second side of the substrate, to produce at least one region of polymerization of varying thickness within the epoxy layer, resulting in a three-dimensional structure with a continuously varying thickness and a smoothly varying topography following removal of non-polymerized regions of the epoxy layer, wherein the three-dimensional structure is at its thickest part at least 100 micrometers.

6. (original) An article of claim 5, wherein the three-dimensional structure is at its thickest part several times thicker than 100 micrometers.

7. (cancelled)